

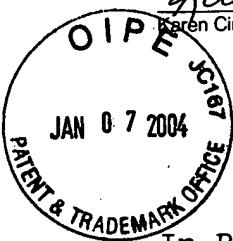
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1/5/04
(Date of Deposit)


Karen Cinq-Mars

(Signature)

1/5/04
(Date)



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of : January 5, 2004

Furukawa et al. :

Serial No. 10/707,009 :

Examiner:

Filed: Herewith :

IBM Corporation
Dept. 18G/Bldg. 300-482
2070 Route 52
Hopewell Junction,
New York 12533-6531

Title: ALTERNATING PHASE MASK BUILT
BY ADDITIVE FILM DEPOSITION :

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under
37 C.F.R. § 1.56 and in accordance with the practice under
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to
the documents listed on the enclosed Form PTO-1449. Copies of the
listed documents are also enclosed.

It is respectfully requested that the above information be
considered by the Examiner and that a copy of the enclosed Form
PTO-1449 be returned indicating that such information has been
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030300

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,

Todd M. C. Li 1/5/04
Todd M. C. Li
Attorney for Applicants
Registration No.45,554

INTERNATIONAL BUSINESS MACHINES CORPORATION
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TML/kcm

FIS920030300

<p style="text-align: center;">O I P INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i></p> <p style="text-align: center;">JAN 07 2004 PATENT & TRADEMARK OFFICE U.S. PATENT AND TRADEMARK OFFICE SC107</p>		Docket Number (Optional) FIS920030300	Application Number 10/707,009																																
		Applicant(s) Furukawa et al.																																	
		Filing Date 11-13-03	Group Art Unit																																
<p style="text-align: center;">OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</p> <table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td style="width: 10%;"></td> <td style="width: 90%;">Homma et al., "A Selective SiO₂ Film-Formation Technology Using Liquid-Phase Deposition for Fully Planarized Multilevel Interconnections", J. Electrochem. Soc., Vol. 140, No. 8, 1993, pp. 2410-2414.</td> </tr> <tr> <td></td> <td>Ching-Fa Yeh, et al., "Comprehensive Investigation on Fluorosilicate Glass Prepared by Temperature-Difference-Based Liquid-Phase Deposition", J. Electrochem. Soc., Vol. 147, No. 1, 2000, pp. 330-334.</td> </tr> <tr> <td></td> <td>Nagayama et al., "A New Process for Silica Coating", J. Electrochem. Soc., Vol. 135, No. 8, 1988, pp. 2013-2016.</td> </tr> <tr> <td></td> <td>Homma et al., "Optical Properties of Fluorinated Silicon Oxide and Organic Spin-on-Glass Films for Thin-Film Optical Waveguides", J. Electrochem. Soc., Vol. 147, No. 3, 2000, pp. 1141-1144.</td> </tr> <tr> <td></td> <td>Ching-Fa Yeh et al., "Novel Barrier Dielectric Liner Prepared by Liquid-Phase Deposition and NH₃ Plasma Annealing", Journal of Appl. Phys. Vol. 39, 2000, pp. 6672-6675.</td> </tr> <tr> <td></td> <td></td> </tr> <tr> <td colspan="2">EXAMINER</td> <td colspan="2">DATE CONSIDERED</td> </tr> <tr> <td colspan="4"> <small>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small> </td> </tr> </table>					Homma et al., "A Selective SiO ₂ Film-Formation Technology Using Liquid-Phase Deposition for Fully Planarized Multilevel Interconnections", J. Electrochem. Soc., Vol. 140, No. 8, 1993, pp. 2410-2414.		Ching-Fa Yeh, et al., "Comprehensive Investigation on Fluorosilicate Glass Prepared by Temperature-Difference-Based Liquid-Phase Deposition", J. Electrochem. Soc., Vol. 147, No. 1, 2000, pp. 330-334.		Nagayama et al., "A New Process for Silica Coating", J. Electrochem. Soc., Vol. 135, No. 8, 1988, pp. 2013-2016.		Homma et al., "Optical Properties of Fluorinated Silicon Oxide and Organic Spin-on-Glass Films for Thin-Film Optical Waveguides", J. Electrochem. Soc., Vol. 147, No. 3, 2000, pp. 1141-1144.		Ching-Fa Yeh et al., "Novel Barrier Dielectric Liner Prepared by Liquid-Phase Deposition and NH ₃ Plasma Annealing", Journal of Appl. Phys. Vol. 39, 2000, pp. 6672-6675.															EXAMINER		DATE CONSIDERED		<small>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>			
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